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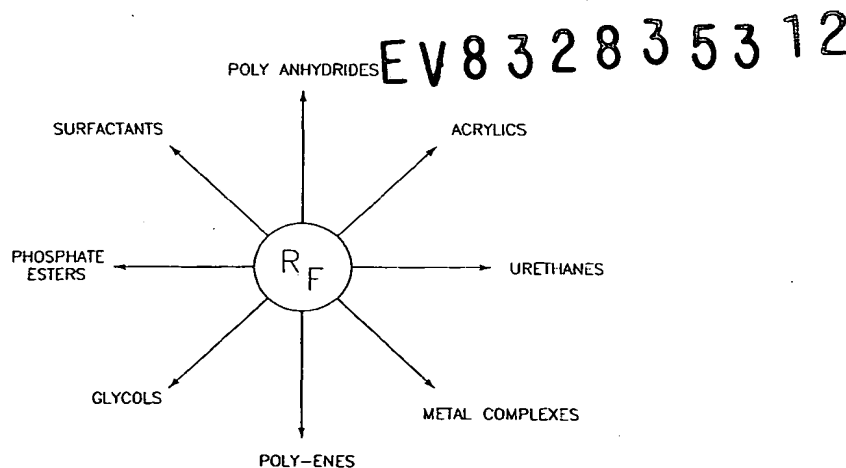
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(54) Title: PRODUCTION PROCESSES AND SYSTEMS, COMPOSITIONS, SURFACTANTS, MONOMER UNITS, METAL COMPLEXES, PHOSPHATE ESTERS, GLYCOLS, AQUEOUS FILM FORMING FOAMS, AND FOAM STABILIZERS



(57) Abstract: Production processes and systems are provided that include reacting halogenated compounds, dehalogenating compounds, reacting alcohol's, reacting olefins and a saturated compounds, reacting reactants having at least two -CF₃ groups with reactants having cyclic groups. R_F-compositions such as R_F-intermediates, R_F-surfactants, R_F-monomers, R_F-monomer units, R_F-metal complexes, R_F-phosphate esters, R_F-glycols, R_F-urethanes, and/or R_F-foam stabilizers. The R_F portion can include at least two -CF₃ groups, at least three -CF₃ groups, and/or at least two -CF₃ groups and at least two -CH₂- groups. Detergents, emulsifiers, paints, adhesives, inks, wetting agents, foamers, and defoamers including the R_F-surfactant composition are provided. Acrylics, resins, and polymers are provided that include a R_F-monomer unit. Compositions are provided that include a substrate having a R_F-composition thereover. Aqueous Film Forming Foam ("AFFF") formulations are provided that can include R_F-surfactants and/or R_F-foam stabilizers are provided.

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